



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant : Timothy J. Brosnihan et al

Art Unit : 2814

Serial No. : 09/342,348

Examiner : Anh D. Mai

Filed : June 29, 1999

Title : METHOD OF FABRICATING A MICROFABRICATED HIGH ASPECT RATIO  
DEVICE WITH ELECTRICAL ISOLATION

Commissioner for Patents  
Washington, D.C. 20231

RESPONSE

In response to the action mailed June 6, 2001, please amend the application as follows:

In the title:

Please amend the title to read: METHOD OF FABRICATING A  
MICROFABRICATED HIGH ASPECT RATIO DEVICE WITH ELECTRICAL ISOLATION.

In the claims:

Please amend the claims as follows:

1. (Amended) A method of fabricating a microelectromechanical system,  
comprising:
- providing a substrate having a device layer;
  - etching a first trench in the device layer, the first trench surrounding a first region  
of the substrate;
  - depositing a dielectric isolation layer in the first trench to electrically isolate the  
first region from a second region of the substrate; and
  - etching a second trench in the device layer, the second trench located in first  
region and defining a microstructure.

CERTIFICATE OF MAILING BY FIRST CLASS MAIL

I hereby certify under 37 CFR §1.8(a) that this correspondence is being  
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